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Sheet 1 of 2711 West Los Altos Road  
Tucson, AZ 85704-4105

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. D-95013A1a	SERIAL NO. (Filed Herewith)		
LIST OF PRIOR ART CITED BY APPLICANT				APPLICANT			
				Ahmad Waleh et al			
				FILING DATE (Filed Herewith)	GROUP		
U.S. PATENT DOCUMENTS							
EXR IN	DOC. NO.	DATE	NAME	CLASS	SUBCLASS		
<u>AA</u>	AA	4,669,544	6/1/87	Nimerick	166 300		
	AB	5,030,399	7/9/91	Walles et al	264 83		
	AC	5,158,100	10/27/92	Tanaka et al	134 105		
	AD	4,179,071	12/18/79	Kozacka	239 397.5		
	AE	4,915,912	4/10/90	Walles et al	422 160		
	AF	4,778,536	10/18/88	Grebinski	134 36		
	AF1	5037506	8/1991	Gupta, et al	134 902		
	AG	4,363,673	12/1982	Settineri, et al	134 2		
	AH	4,455,175	06 <del>12</del> /1984	Settineri, et al	134 5		
	AI	4,536,222	8/1985	Settineri, et al	134 5		
	AJ	5,763,016	06 <del>12</del> /1998	Levinson, et al	427 510		
	AK	5,952,157	9/1999	Kato, et al	430 329		
<u>AL</u>	AL	5,227,001	7/13/93	Tamaki, et al	156 345		
FOREIGN PATENT DOCUMENTS							
	DOC. NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	AN						
	AO						
	AP						
OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
<u>AR</u>	AR	Stanley Wolf and Richard N. Tauber, "Silicon Processing For The VLSI Era", <i>Process Technology</i> , Vol. 1 (1986), p. 564;					
	AS	"Choose The Right Process To Strip Your Photoresist", <i>Semiconductor International</i> , February 1990, pp 83-87;					
	AT	"New Concerns In Dry Oxygen Ashing", <i>Semiconductor International</i> , March 1996, p. 44; and					
	AU	"What's Driving Resists Dry Stripping?", <i>Semiconductor International</i> , November 1994, pp 61-64.					
	AV	Christina M. Cline, "Emerging Technology; Emerging Markets", <i>Precision Cleaning</i> , October 1996, pp 11-19					
<u>AW</u>	AW	Ruth DeJule, "Managing Etch and Implant Residue", <i>Semiconductor International</i> , August 1997, pp 56-63					
EXAMINER			DATE CONSIDERED				
<u>A. MARUCCI</u>			<u>10/28/07</u>				
EXAMINER: Initial if references considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

Change(s) applied  
to document,  
/G.H./  
8/16/2011